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INFORMATION DISCLOSURE
STATEMENT BY APPLICANT

(Use several sheets if necessary)

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Applicants

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Filing Date

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Group

U. S. PATENT DOCUMENTS

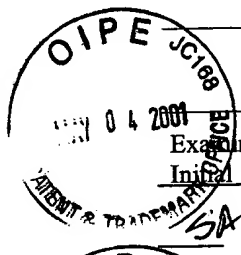
Examiner Initial	Document Number	Issue Date	Name	Class	Subclass	Filing Date If Appropriate
<u>SA</u>	5,186,718	02/16/93	Tepman et al.	29	25.01	
<u>SA</u>	5,789,320	08/04/98	Andricacos et al.	438	678	
<u>SA</u>	6,030,666	02/29/00	Lam et al.	427	539	
<u>SA</u>	6,046,116	04/04/00	De Ornellas et al.	438	715	
<u>SA</u>	6,087,265	07/11/00	Hwang	438	706	

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FOREIGN PATENT DOCUMENTS

Examiner Initial	Document Number	Publication Date	Name	Class	Subclass	Translation If Appropriate
SA	DD 142966	07/23/80	Schade et al.	C23C	15/00	Abstract
SA	DD 285224	12/05/90	Geiler et al.	H01L	21/265	Abstract
SA	JP 53109475	09/25/78	Hitachi Ltd.	H01L	21/203	Abstract
SA	JP 1088345	04/07/98	Sukegawa Elec.	C23C	14/50	Abstract

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, etc.)

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